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(19) **United States**(12) **Patent Application Publication**
Park(10) **Pub. No.: US 2008/0278645 A1**(43) **Pub. Date: Nov. 13, 2008**(54) **LIQUID CRYSTAL DISPLAY AND
MANUFACTURING METHOD THEREOF****Publication Classification**(76) Inventor: **Jiryun Park, Yongin-si (KR)**

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PASADENA, CA 91109-7068 (US)(51) **Int. Cl.****G02F 1/1343** (2006.01)**G02F 1/13** (2006.01)(52) **U.S. Cl. 349/38; 349/187**(57) **ABSTRACT**

A liquid crystal display and a manufacturing method thereof. The liquid crystal display includes a storage capacitor having a metal electrode as a reflector. The liquid crystal display may include a color filter and/or a black matrix on a reflective region of a second substrate corresponding to the storage capacitor on a first substrate. Light is reflected from the reflective region to transmit through liquid crystals between the first and second substrates. An organic film may be on the second substrate.

(21) Appl. No.: **12/117,717**(22) Filed: **May 8, 2008**(30) **Foreign Application Priority Data**

May 11, 2007 (KR) 10-2007-0046108

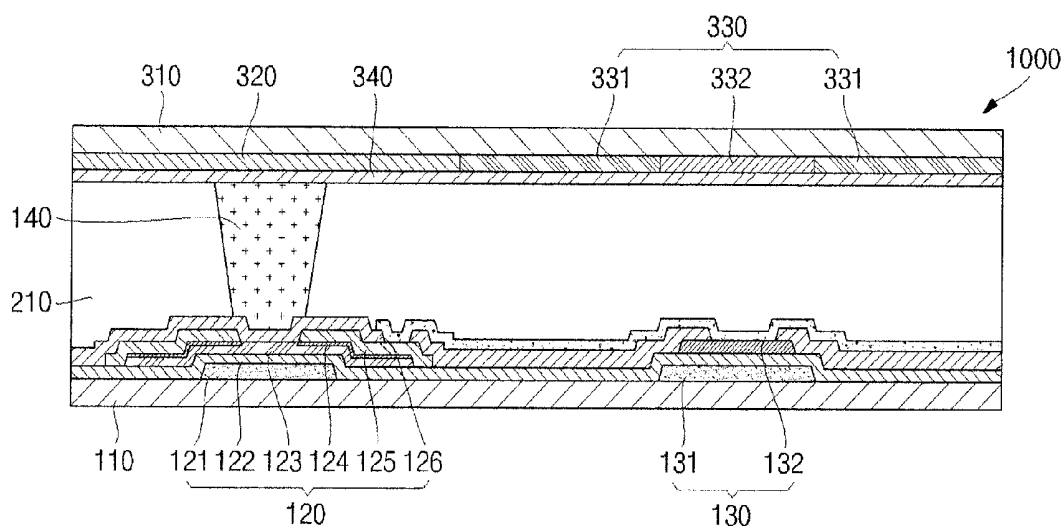


FIG.1

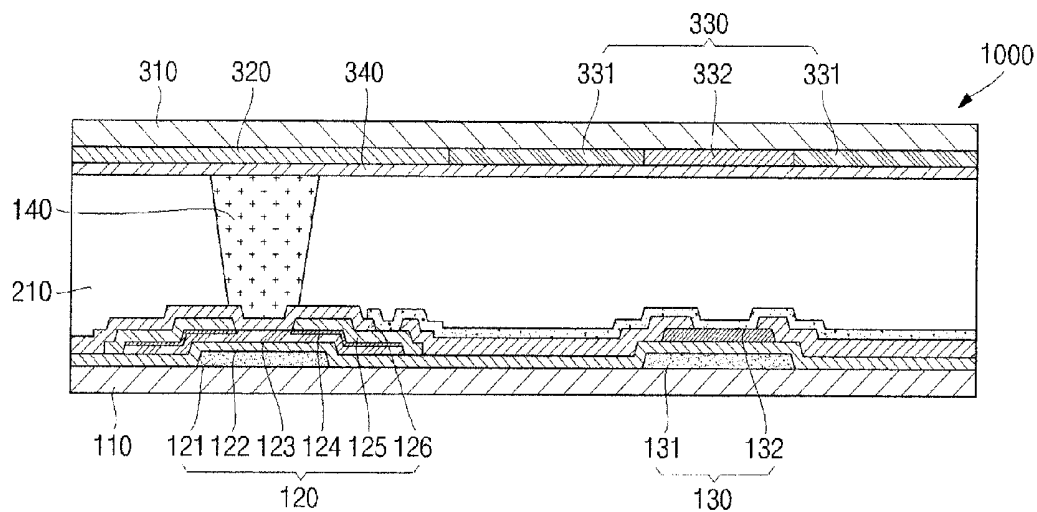


FIG.2

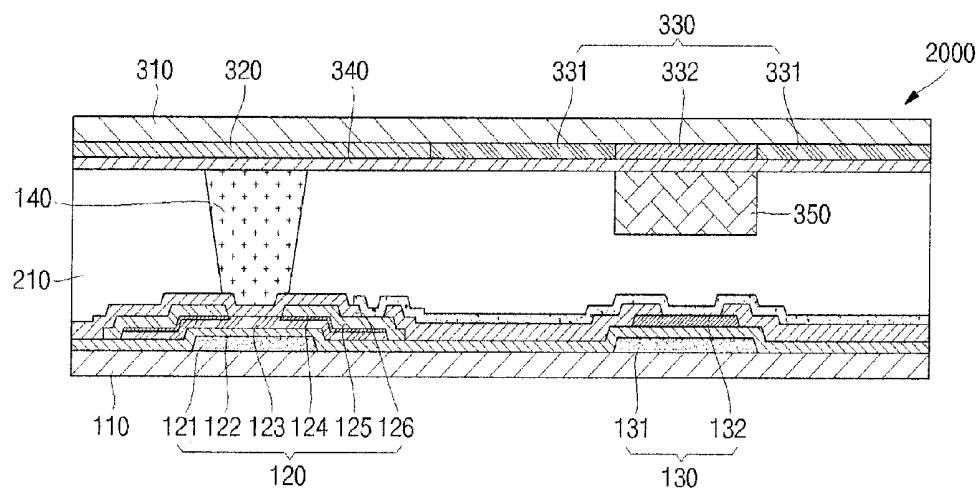


FIG.3

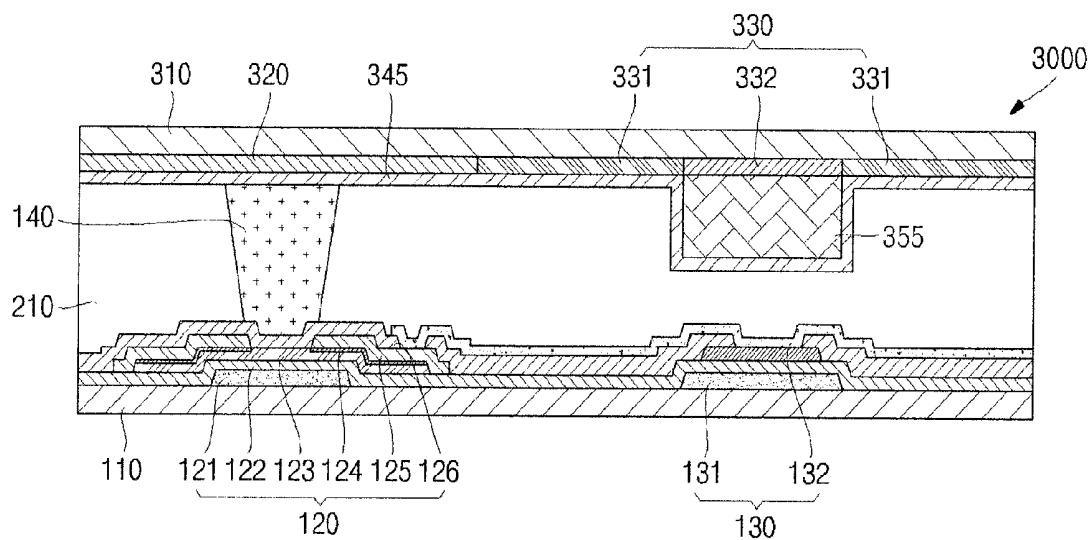


FIG.4

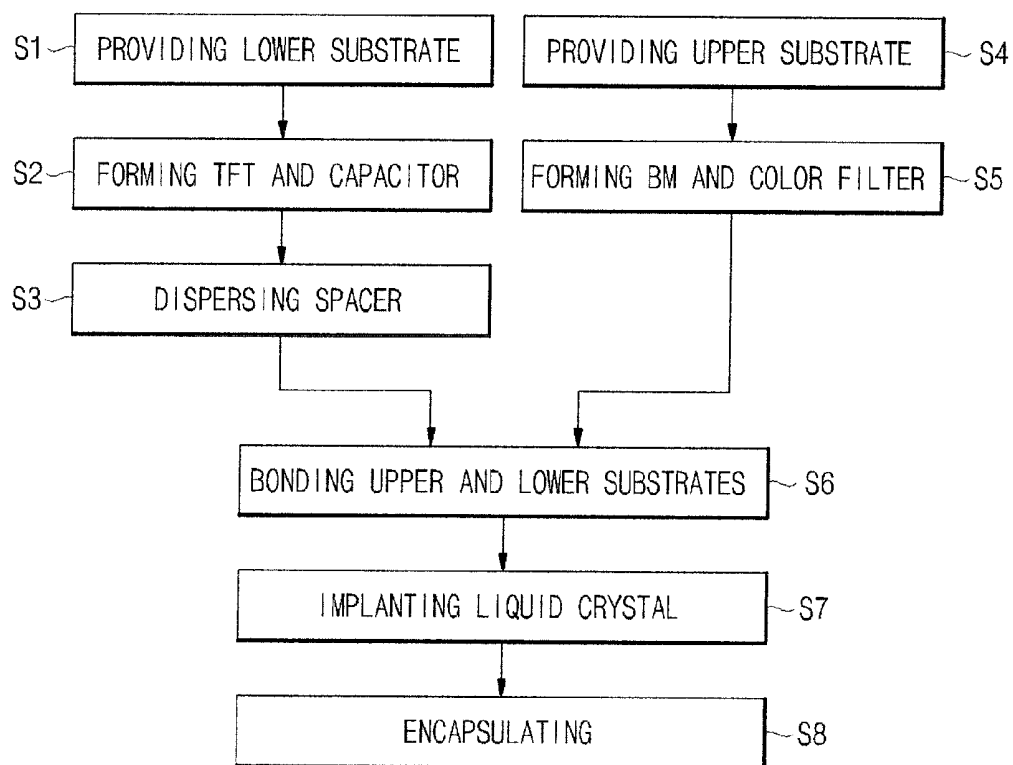


FIG.5a

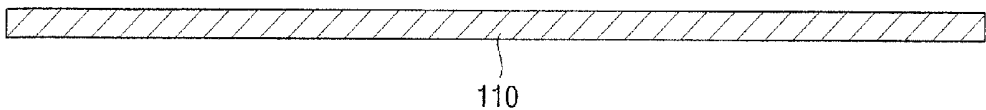


FIG.5b

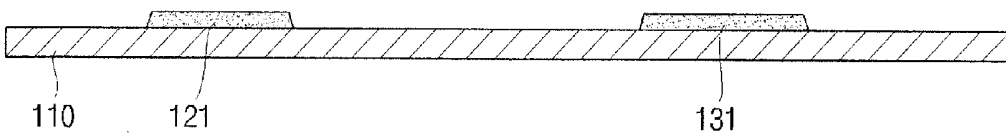


FIG.5c

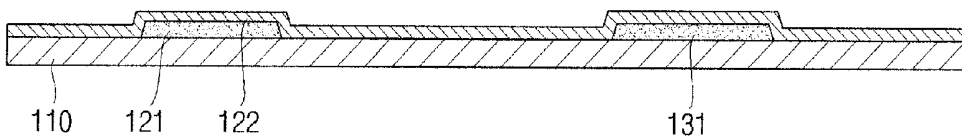


FIG.5d

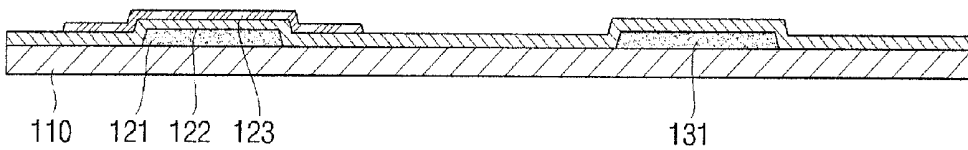


FIG.5e

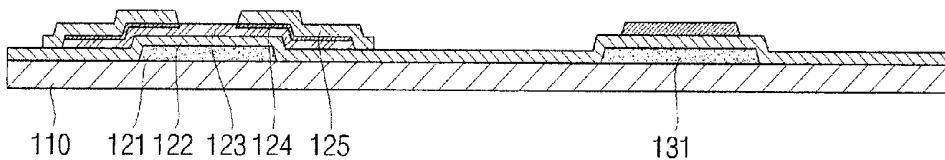


FIG.5f

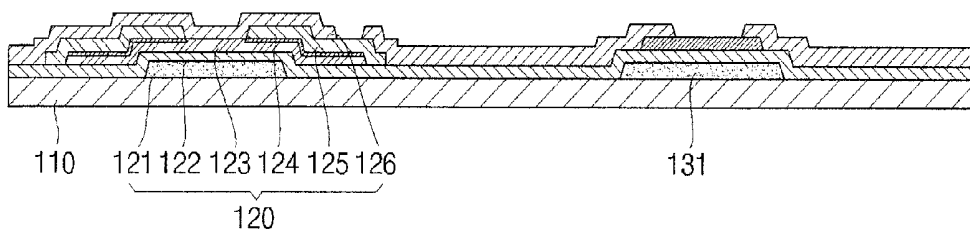


FIG.5g

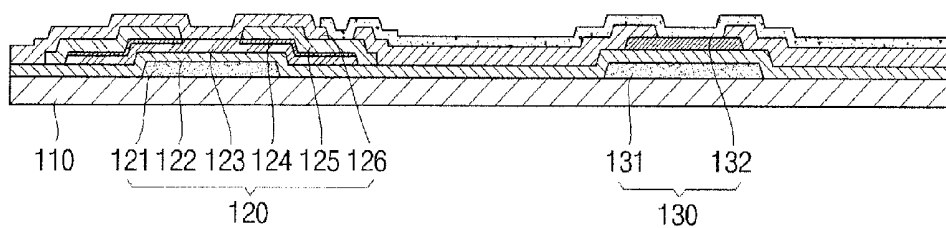


FIG.5h

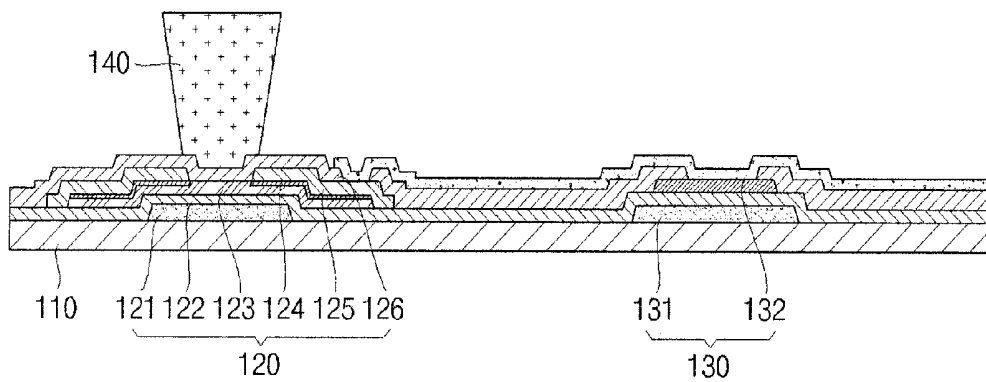


FIG.5i

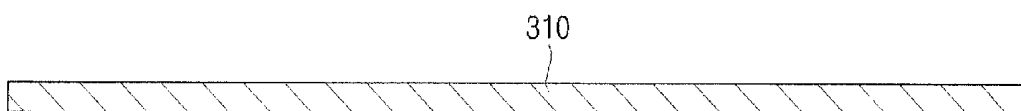


FIG.5j

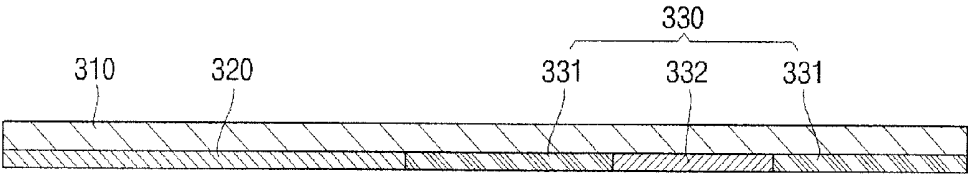


FIG.5k

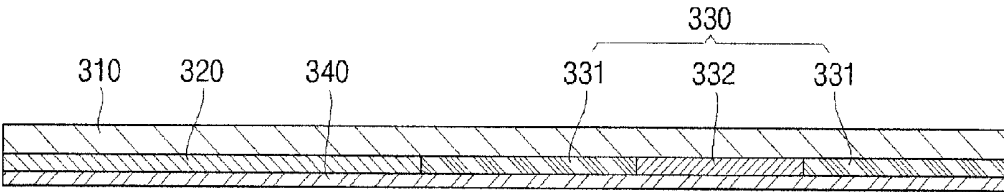


FIG.5l

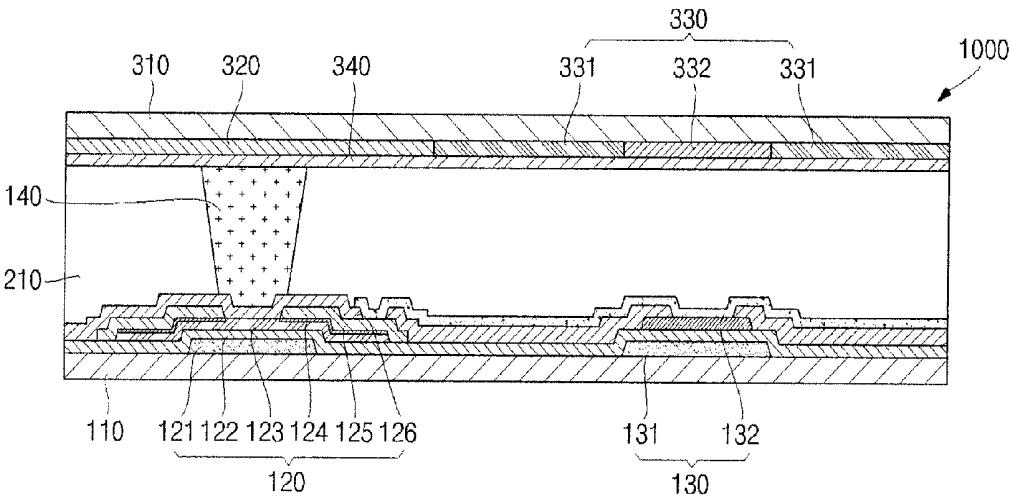


FIG.6

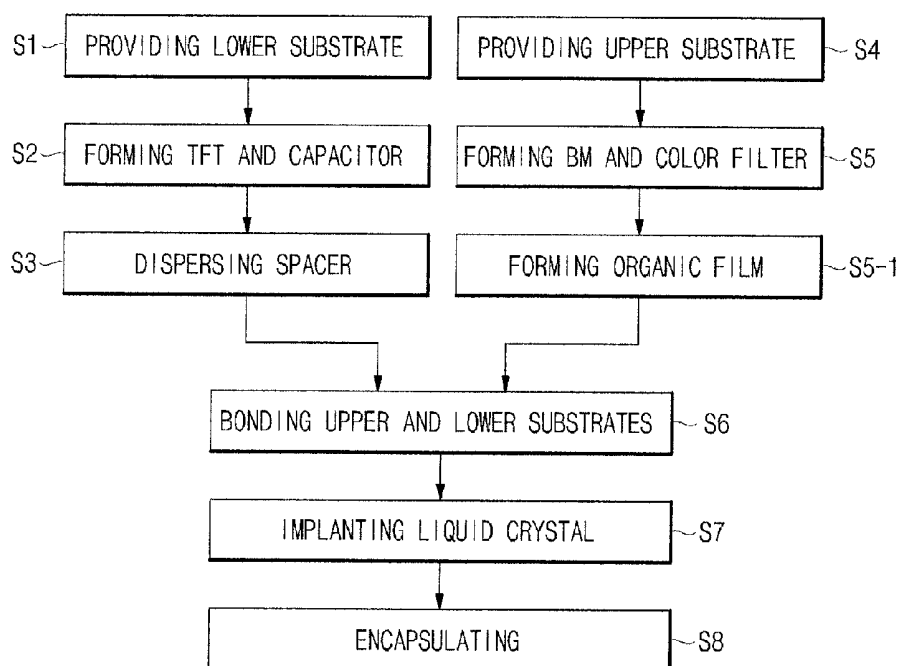


FIG.7a



FIG.7b

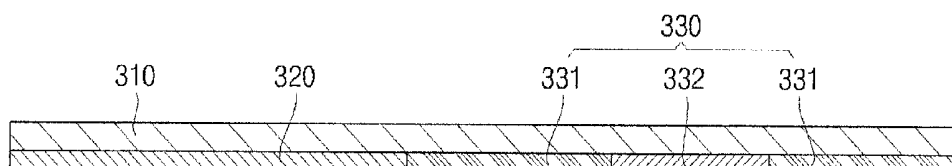


FIG. 7c

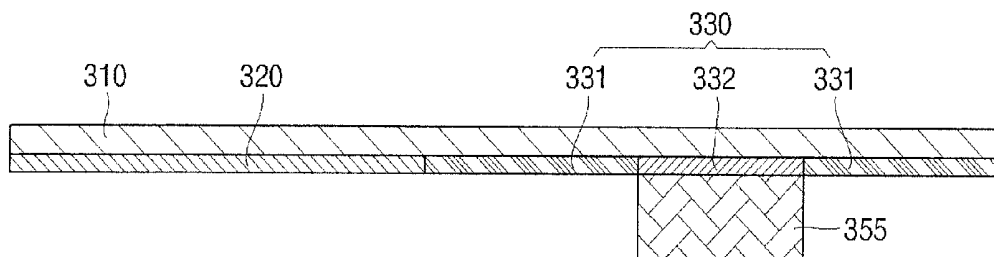


FIG. 7d

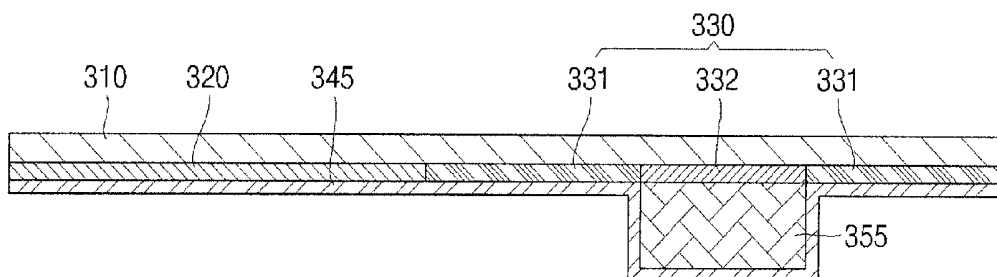
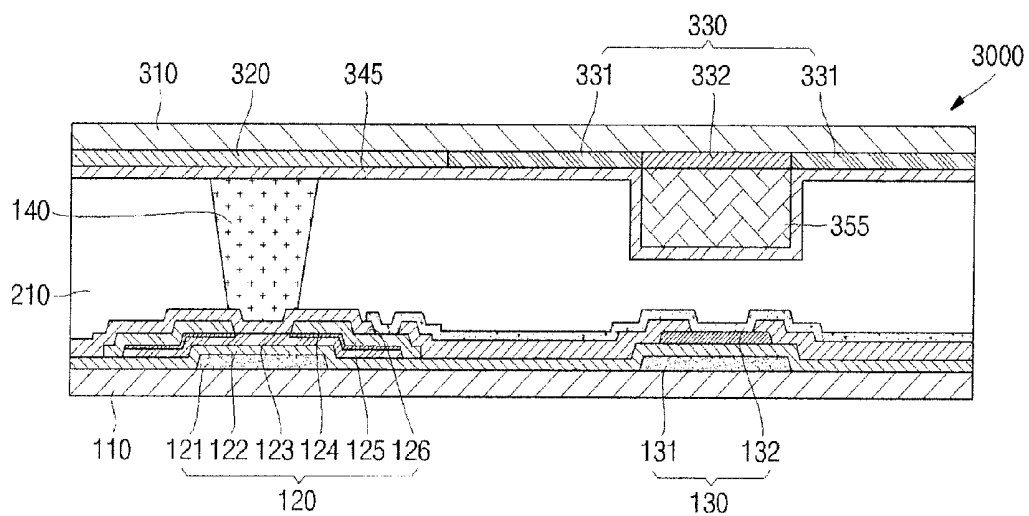


FIG. 7e



LIQUID CRYSTAL DISPLAY AND MANUFACTURING METHOD THEREOF

CROSS-REFERENCE TO RELATED APPLICATION

[0001] This application claims priority to and the benefit of Korean Patent Application No. 10-2007-0046108, filed on May 11, 2007, the entire content of which is incorporated herein by reference.

BACKGROUND OF THE INVENTION

[0002] 1. Field of the Invention

[0003] The present invention relates to a liquid crystal display and a manufacturing method thereof.

[0004] 2. Description of the Related Art

[0005] In general, a liquid crystal display may be classified as a transmissive liquid crystal display that uses a backlight as a light source and a reflective liquid crystal display that uses natural light as a light source. The transmissive liquid crystal display uses the backlight as the light source so that it can produce a bright image even in a dark environment. However, in a bright environment, it is difficult to operate the transmissive liquid crystal display, and it consumes a large amount of power.

[0006] On the other hand, since the reflective liquid crystal display does not include a backlight, it reduces power consumption, but it can not be used when the environment is dark.

[0007] As an alternative, a transreflective liquid crystal display can overcome the above described restriction of the reflective liquid crystal display. The transreflective liquid crystal display has both a reflective region and a transmission region within a unit pixel so that it can be used as both a reflective type liquid crystal display and a transmissive liquid crystal display, as needed.

[0008] A typical transreflective liquid crystal display includes a separate reflective electrode that reflects light to the reflective region. Generally, a masking process is required so as to form the separate reflective electrode, wherein seven to nine masks are generally used. Since the transreflective liquid crystal display uses more masks as compared to the transmissive liquid crystal display that uses four to five masks, the manufacturing cost of the transreflective liquid crystal display is higher.

SUMMARY OF THE INVENTION

[0009] It is an aspect according to an embodiment of the present invention to provide a liquid crystal display and a manufacturing method thereof, which does not require a separate reflective electrode by using a metal electrode of a storage capacitor as a reflector.

[0010] It is another aspect according to an embodiment of the present invention to provide a liquid crystal display and a manufacturing method thereof capable of displaying images by including an optional color filter in a reflective region of an upper substrate. The reflective region includes no black matrix and corresponds to a storage capacitor on a lower substrate that reflects light.

[0011] It is another aspect of the present invention to provide a liquid crystal display and a manufacturing method thereof capable of improving the image quality of a reflective region by forming an organic film for a dual cell gap structure in the reflective region of an upper substrate corresponding to a storage capacitor on a lower substrate.

[0012] In addition, it is still another aspect of the present invention to provide a manufacturing method of a transreflective liquid crystal display capable of being made at a low cost.

[0013] According to one embodiment of the present invention, a liquid crystal display is provided. The liquid crystal display includes: a first substrate; a second substrate facing the first substrate; a thin film transistor on a side facing the second substrate of the first substrate; a storage capacitor on the side facing the second substrate of the first substrate; a black matrix on a side facing the first substrate of the second substrate; a color filter on the side facing the first substrate of the second substrate; and liquid crystals between the first substrate and the second substrate, wherein the storage capacitor includes a reflective electrode configured to reflect external light received through the first substrate.

[0014] The storage capacitor may further include a pixel electrode. The reflective electrode of the storage capacitor may include any one selected from Al, AlNd, Mo, Cr, Mo/AlNd(double), MoW, and equivalents thereof.

[0015] The color filter may be on a reflective region of the second substrate, and the reflective region corresponds to the storage capacitor on the first substrate.

[0016] The black matrix may be on a region of the second substrate that is different from a reflective region of the second substrate, and the reflective region corresponds to the storage capacitor on the first substrate.

[0017] According to another embodiment of the present invention, a liquid crystal display is provided. The liquid crystal display includes: a first substrate; a second substrate facing the first substrate, a thin film transistor on a side facing the second substrate of the first substrate; a storage capacitor on the said facing the second substrate of the first substrate, the storage capacitor including a reflective electrode configured to reflect external light received through the first substrate; a black matrix on a side facing the first substrate of the second substrate; a color filter on the side facing the first substrate of the second substrate; an organic film on a reflective region of the second substrate, the reflective region corresponding to the storage capacitor on the first substrate; and liquid crystals between the first substrate and the second substrate.

[0018] The organic film may be on the color filter in the reflective region. The organic film may be on the reflective region of the second substrate that is different from another region of the second substrate in which the black matrix and the color filter are located.

[0019] The liquid crystal display may further include a common electrode on the black matrix and the color filter, and the organic film is on the common electrode. The common electrode may be on the black matrix, the color filter and the organic film.

[0020] A thickness of the organic film may be one half the total thickness of the liquid crystals. The organic film may provide a path traveled by a reflected light through the liquid crystals in the reflective region, wherein a distance traveled by the reflected light within the liquid crystals is equal to a distance traveled by a transmitted light within the liquid crystals in a transmission region.

[0021] According to yet another embodiment of the present invention, a manufacturing method of a liquid crystal display is provided. The method includes: forming a thin film transistor and a storage capacitor on a first substrate, the storage capacitor having a reflective electrode; providing a second substrate facing the first substrate, forming a black matrix and

a color filter on a side facing the first substrate on the second substrate; bonding the lower substrate and the second substrate together; and implanting liquid crystals between the bonded first and second substrates.

[0022] The storage capacitor may further include a pixel electrode. The reflective electrode of the storage capacitor may include any one selected from Al, AlNd, Mo, Cr, Mo/AlNd(double), MoW, or equivalents thereof.

[0023] The color filter may be on a reflective region of the second substrate, and the reflective region corresponds to the storage capacitor on the first substrate.

[0024] The black matrix and the color filter may be on a region of the second substrate other than the reflective region corresponding to the storage capacitor on the first substrate.

[0025] According to still another embodiment of the present invention, a manufacturing method of a liquid crystal display is provided. The method includes: forming a thin film transistor and a storage capacitor on a first substrate, the storage capacitor including a reflective electrode; forming a black matrix and a color filter on a side facing the first substrate on a second substrate; forming an organic film on a reflective region on the side facing the first substrate of the second substrate, the reflective region corresponding to the storage capacitor on the first substrate; bonding the first substrate and the second substrate together; and implanting liquid crystals between the bonded upper and lower substrates.

[0026] The organic film may be on the color filter in the reflective region and the organic film corresponds to the storage capacitor.

[0027] The organic film may be on the reflective region, and the black matrix and the color filter are on a region different from the reflective region.

[0028] The method may further provide a common electrode, wherein the common electrode is on the black matrix and the color filter, and the organic film is on the common electrode.

[0029] The method may further provide a common electrode on the black matrix, the color filter, and the organic film.

[0030] A thickness of the organic film may have half of the total thickness of the liquid crystals.

[0031] The organic film may provide a path traveled by a reflected light through the liquid crystals in the reflective region, wherein a distance traveled by the reflected light within the liquid crystals is equal to a distance traveled by a transmitted light within the liquid crystals in a transmission region.

[0032] Hereinafter, exemplary embodiments of the present invention will be described below with reference to the accompanying drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

[0033] The above and other aspects and features of the present invention will be more apparent from the following detailed description taken in conjunction with the accompanying drawings, in which:

[0034] FIG. 1 is a cross-sectional view illustrating a liquid crystal display according to one exemplary embodiment of the present invention;

[0035] FIG. 2 is a cross-sectional view illustrating a liquid crystal display according to another exemplary embodiment of the present invention;

[0036] FIG. 3 is a cross-sectional view illustrating a liquid crystal display according to yet another exemplary embodiment of the present invention;

[0037] FIG. 4 is a flow diagram for explaining a manufacturing method of a liquid crystal display according to one exemplary embodiment of the present invention;

[0038] FIGS. 5a to 5f are cross-sectional views for illustrating a manufacturing method of a liquid crystal display according to one exemplary embodiment of the present invention;

[0039] FIG. 6 is a flow diagram for explaining a manufacturing method of liquid crystal displays according to another exemplary embodiment and other exemplary embodiments of the present invention.

[0040] FIGS. 7a to 7e are cross-sectional views for illustrating an exemplary manufacturing method of a liquid crystal display according to yet another exemplary embodiment of the present invention.

DETAILED DESCRIPTION OF THE EMBODIMENTS

[0041] A liquid crystal display according to one exemplary embodiment of the present invention will be described.

[0042] FIG. 1 is a cross-sectional view illustrating a liquid crystal display 1000 according to an exemplary embodiment of the present invention.

[0043] As shown in FIG. 1, the liquid crystal display 1000 according to the exemplary embodiment of the present invention includes a lower substrate 110, a thin film transistor 120, a storage capacitor 130, a spacer 140, a liquid crystal 210, an upper substrate 310, a black matrix 320, a color filter 330, and a common electrode 340.

[0044] The lower substrate 110 is an original plate on which the thin film transistor 120 is formed. Since the light of a backlight unit (BLU) is transmitted through the lower substrate 110, the material of the lower substrate 110 should be transparent. Accordingly, it is generally made of glass, and its thickness is generally about 0.5 to 0.7 mm. A fusion method and a floating method have largely been used as a method of making the glass for the lower substrate 110.

[0045] In the floating method, the glass for the substrate 110 is made by flowing a melted glass that is boiled in a melting furnace into a horizontal roller (melted tin). However, in the floating method the glass contacts the roller so that a further process is needed for polishing the glass later.

[0046] In the fusion method, a melted glass is cooled by letting it fall vertically in the air after it flows out of a melting furnace. Accordingly, the fusion method has an advantage that the surface quality of the glass is improved because no contact to the surface of the melted glass is made when the melted glass is formed.

[0047] The thin film transistor 120 includes: a gate electrode 121 formed on the upper side of the lower substrate 110; a gate insulating layer 122 formed on the lower substrate 110 and the upper side of the gate electrode 121; a silicon layer 123 formed on the upper side of the gate insulating layer 122; a semiconductor layer 124 formed on the upper side of the silicon layer 123; a source/drain electrode 125 formed on the upper side of the semiconductor layer 124; and a protective layer 126 on the source/drain electrode 125 and the upper side of the gate insulating layer 122.

[0048] The gate electrode 121 is formed on the lower substrate 110, wherein it is formed on the same layer as the lower electrode 131 of the storage capacitor 130. According to an exemplary embodiment of the present invention, the lower electrode 131 of the capacitor functions as a reflective electrode. Accordingly, the lower electrode 131 of the storage

capacitor **130**, as will be described below, may be made of Al, AlNd, Mo, Cr, Mo/AlNd(double), MoW or an equivalent thereof.

[0049] The gate electrode **121** is generally formed using a sputtering method. The sputtering method uses argon cation (Ar⁺) accelerated using high voltage. When kinetic energy of the argon cation (Ar⁺) is larger than bond energy between metal atoms, the sputtering method separates atoms from the metal surface. The sputtered metal atoms consumes their energy through their mutual collision and interference and are mutually bonded at a surface of a glass substrate to be grown in a thin film form. However, the present invention is not limited to the material and manufacturing methods of the gate electrode **121** described above.

[0050] The gate insulating layer **122** is formed over the gate electrode **121** and the lower substrate **110**. The gate insulating layer **122** provides insulation function between the gate electrode **121** and the source/drain electrode **125** and is generally deposited using, for example, silicon nitride (SiN_x).

[0051] The gate insulating layer **122** is generally formed using a plasma enhanced chemical vapor deposition (PECVD) method. The PECVD method is a process that includes: implanting chemical vapor into a chamber in a vacuum state, resolving gas molecules by colliding electrons that obtain high energy using an electric field with gas molecules in neutral state, and depositing a thin film by using a reaction for attaching the resolved gas atoms to the substrate. However, the present invention is not limited to the material and manufacturing methods of the gate insulating layer **122** as described above.

[0052] The silicon layer **123** is formed on the gate insulating layer **122**. A channel is formed on the silicon layer **123** when voltage is applied to the gate electrode **121**, and the silicon layer **123** is typically formed using the PECVD method.

[0053] The silicon layer **123** is typically formed using, for example, amorphous silicon (a-Si) because the glass of the lower substrate **110** is amorphous, and poly silicon (poly-Si) may be formed in order to increase electron mobility. The poly silicon (poly-Si) is formed by growing grains by depositing the amorphous silicon (a-Si) on the substrate and then heating the substrate. The poly silicon (poly-Si) is divided into low temperature poly silicon (LTPS) and high temperature poly silicon (HTPS) depending on process temperature.

[0054] Regarding crystallization methods, some examples are a solid phase crystallization (SPC) method, a field enhanced rapid thermal annealing (FERTA) method, an excimer laser annealing (ELA) method, a sequential lateral solidification (SLS) method, a metal induced crystallization (MIC) method, a metal induced lateral crystallization (MILC) method, a super grain silicon (SGS) method, etc.

[0055] However, the silicon layer **123** is not limited to the material and manufacturing methods of the silicon layer **123** as described above.

[0056] The semiconductor layer **124** is formed on the upper side of the silicon layer **123**. The semiconductor layer **124** is formed by doping impurities into a desired portion in a region of the silicon layer **123** using a mask. The impurities that are implanted into the semiconductor layer **124** may include group III elements and group V elements. However, since electron mobility is larger than hole mobility, the group III elements are mainly used to form an N-type semiconductor.

[0057] As a method of doping the impurities into the semiconductor layer **124**, an ion implantation method is typically

used. Using the ion implantation method, a semiconductor device is manufactured by implanting impurity ions. The ion implantation method can be used to implant the impurity ions even at room temperature, control the amount of impurity ions implanted precisely and uniformly, heat-treat the impurity sufficiently at the temperature of 1000° C. or less, and control a thickness of an implantation layer with acceleration voltage of ions, etc. However, the present invention is not limited to the material and manufacturing methods of the semiconductor layer **123** as described above.

[0058] The source/drain electrode **125** is formed on the upper side of the semiconductor layer **124**. The source/drain electrode **125** is deposited over the lower substrate and is then formed in a desired pattern using a mask. The source/drain electrode **125** can be made of the same material as the gate electrode **121**. Thereafter, the source/drain electrode **125** is electrically connected to the pixel electrode **132**.

[0059] The protective layer **126** is formed on the source/drain electrode **125** and the upper side of the silicon layer **123**. The protective layer **126** protects the main portions of the pixel and the silicon layer **123** of the thin film transistor **120** against moisture or scratch which can be generated in a subsequent process. Accordingly, silicon nitride (SiN_x) with high transmittance, moisture resistance, and durability is deposited as the protective layer **126** using the PECVD method. However, the present invention is not limited to the material and manufacturing methods of the protective layer **126** as described above.

[0060] The storage capacitor **130** is electrically connected to the thin film transistor **120**. The storage capacitor **130** stores data values as a voltage supplied through the thin film transistor **120** and constantly maintains the voltage across the liquid crystal **210**. Thereby, the liquid crystal display **1000** can maintain a desired brightness (e.g., a predetermined brightness) for one frame of an image.

[0061] The storage capacitor **130** is constituted by the lower electrode **131** and the pixel electrode **132**.

[0062] The lower electrode **131** is formed on the lower substrate **110** and can be formed using the same process as the gate electrode **121**. In a conventional liquid crystal display, light cannot travel through a lower electrode of a storage capacitor. Accordingly, in the upper substrate of the conventional liquid crystal display, a reflective region corresponding to the portion formed with the lower electrode is formed with a black matrix. Also, since this black matrix occupies a portion of the pixels, the aperture ratio of the conventional liquid crystal display is lowered.

[0063] The lower electrode **131** according to an embodiment of the present invention functions as a reflective electrode that reflects the external light so that it can improve brightness. The lower electrode **131** according to embodiments of the present invention can be manufactured by using any one selected from Al, AlNd, Mo, Cr, Mo/AlNd(double), and MoW, or the equivalent thereof, which can reflect the external light.

[0064] Also, in the liquid crystal display **1000** according to the embodiment of the present invention as will be described further below, in the upper substrate **310**, the black matrix **320** is not located in the reflective region corresponding to the lower electrode **131**. The reflective region is formed with the color filter **330** instead of the black matrix **320**. In other words, light can travel through the reflective region, unlike the conventional liquid crystal display described above.

[0065] Accordingly, in the liquid crystal display 1000, the external light is reflected from the lower electrode 131 of the storage capacitor 130, and the reflected external light travels through the transparent upper substrate 310 and/or the color filter 330 formed on the upper substrate 310, thereby making it possible to improve the aperture ratio. In other words, unlike the conventional liquid crystal display, in the liquid crystal display 1000, the black matrix 320 is not located in (or is removed from) a region of the pixels corresponding to the lower electrode 131 that reflects the external light, thereby making it possible to increase the aperture of the liquid crystal display 1000.

[0066] Furthermore, the liquid crystal display 1000 according to the embodiments of the present invention uses the lower electrode 131 of the storage capacitor 130 as the reflective electrode so that it include no separate reflective electrode, thereby making it possible to remove the step of forming the mask for forming the separate reflective electrode.

[0067] The pixel electrode 132 is formed over the upper side of the protective layer 126 after forming the protective layer 126. However, since the pixel electrode 132 is formed only in the region for transmitting light, it is formed only in the region other than the region in which the thin film transistor 120 is formed, as shown in FIG. 1. the pixel electrode 132 is generally formed with a thickness of about 0.1 to 0.3 μm .

[0068] However, the pixel electrode 132 should be electrically connected to the source/drain electrode 125 of the thin film transistor 120. Accordingly, the upper side of the source/drain electrode 125 is electrically connected with the pixel electrode 132 via a contact hole that is formed by etching the protective layer 126.

[0069] Since light travels through the pixel electrode 132, it is formed of a transparent material. The material of the pixel electrode 132 can have a light transmittance of about 80% in the wavelength range of visible light (e.g., 400 nm to 700 nm) and a high conductivity approximately up to 10^3 [S/cm]. For example, the material of the pixel electrode 132 may be indium tin oxide (ITO), tin oxide (SnO_2), or zinc oxide (ZnO), etc. Among these exemplary material, the indium tin oxide (ITO) is primarily used. However, the present invention is not limited to the material of the pixel electrode 132.

[0070] As described above, in the liquid crystal display 1000, the lower electrode 131 of the storage capacitor 130 is used as the reflective electrode, and the black matrix 320 is not located (or formed) in from the portion of the upper substrate 310 that corresponds to the storage capacitor 130, thereby making it possible to increase brightness. In one embodiment, the color filter 330 is located on the portion of the upper substrate that corresponds to the storage capacitor 130.

[0071] Although not shown in FIG. 1 separately, an alignment film is printed on the thin film transistor 120 and the pixel electrode 132. The alignment film controls the aligning and movement of the liquid crystal 210. The alignment film aligns the liquid crystal 210 in a single direction to obtain a uniform screen and improves overall display quality of the liquid crystal display 1000 by allowing the liquid crystal 210 to rapidly react in a single direction in response to an external electric field. The alignment film can be a twisted nematic (TN) type that can be applied in devices such as cellular phone, general purpose monitor, or a notebook computer, etc. The alignment film can also be a vertical alignment type, or an

in plane switching type that can be applied to devices such as a large monitor or liquid a crystal display (LCD) TV, etc.

[0072] Thereafter, a rubbing process is performed. The rubbing process is a process that aligns the liquid crystal 210 by rubbing the alignment film with a rubbing cloth in constant force, speed, and direction to generate a valley. Also, the visible direction of an LCD according to the application of the LCD is also determined in the rubbing process.

[0073] The spacer 140 is formed on the upper side of the protective layer 126 as shown in FIG. 1. In other words, The spacer 140 is the last component formed in the manufacturing process of the lower substrate 110. The spacer 140 is provided to constantly maintain a gap between the lower substrate 110 and the upper substrate 310. Since the spacer 140 is generally formed of an opaque material, it is formed on the upper side of the thin film transistor 120 in order to raise the aperture ratio of the liquid crystal display 1000.

[0074] The spacer 140 should be dispersed to have a substantially constant dispersion rate. As to dispersion methods, there are a dry method and a wet method. The wet method is excellent for dispersion; however, the dry method is primarily used because of environment issues. There are several dry methods. Among the dry methods, an electrostatic dispersion method has been commonly used.

[0075] The liquid crystal 210 is disposed between the lower substrate 110 and the upper substrate 310. In the structure shown in FIG. 1, the liquid crystal 210 is located at an intermediate layer, however in the actual process it is implanted (or injected) after the bond of the upper substrate 310 and the lower substrate 110 is made.

[0076] The liquid crystal 210 is a material having both viscosity as a liquid and crystallinity of a solid. When a voltage is applied, the liquid crystal 210 is arranged as bar-like crystals with a size of several tens of $\text{\AA}$ in the voltage applying direction, and when voltage is not applied, the liquid crystal 210 returns to its original state. The liquid crystal 210 has a continuum property, that is, when a deformation is generated when force is applied to any one point of the liquid crystal 210, it affects neighboring molecules. Also, the liquid crystal 210 has the bar-like crystalline shape so that it has a certain direction at the time of applying the voltage according to a difference in permittivity between a major axis and a minor axis, thereby making it possible to perform a function of a shutter.

[0077] Some exemplary embodiments of the liquid crystal 210 includes a nematic liquid crystal, a smectic liquid crystal, and a cholesteric liquid crystal, etc. However, the present invention is not limited to any particular type of liquid crystal.

[0078] The upper substrate 310 is similar to the lower substrate 110. In more detail, the upper substrate 310 is a glass capable of transmitting light and is the same as the lower substrate 110, except that the black matrix 320, the color filter 330, and the common electrode 340 are formed on the upper substrate 310. Therefore, the description thereof will be omitted.

[0079] The black matrix 320 is formed between the liquid crystal 210 and the upper substrate 310 as shown in FIG. 1. In the actual process, since the upper substrate 310 is provided with the black matrix 320 and then bonded to the lower substrate 110, the black matrix 320 is formed on the upper substrate 310. The black matrix 320 is formed in the region where no light is transmitted to improve the contrast of the red (R), green (G), and blue (B) pixels. In some embodiments, the black matrix 320 may be formed using material such as Cr,

Cr/CrO_x bilayer, carbon pigment, RGB mixing pigment, and graphite, etc. The black matrix 320 is formed in a region corresponding to the thin film transistor 120 in the upper substrate 310, where the region does not transmit light.

[0080] A first method of forming the black matrix 320 includes depositing an opaque metal with low reflection characteristic such as Cr and then patterning it. A second method of forming the black matrix 320 includes coating the upper substrate 310 with a photosensitive black resin and then exposing and etching it. However, the present invention is not limited to the material and manufacturing methods of the black matrix 320.

[0081] In a conventional liquid crystal display, the black matrix 320 is formed even in the reflective region corresponding to the lower electrode 131 of the storage capacitor 130 in the upper substrate 310. Since the storage capacitor 130 is formed in the pixel region, if the black matrix 320 is formed in a portion of the pixel region as described above, the aperture ratio of the conventional liquid crystal display is lowered.

[0082] In the liquid crystal display 1000, the lower electrode 131 of the storage capacitor 130 functions as the reflective electrode as described above. Accordingly, the black matrix 320 is not formed in the reflective region corresponding to the lower electrode 131 of the storage capacitor 130 in the upper substrate 310. The color filter 330 is formed instead of the black matrix 320 so that the external light reflected from the lower electrode 131 can be transmitted through the upper substrate 310. Thereby, the liquid crystal display 1000 has an improved aperture ratio.

[0083] The color filter 330 is formed in the region capable of transmitting light in the upper substrate 310. Since the liquid crystal display 1000 is a non-emissive type display that displays images using light emitted from a backlight unit (BLU), the color filter 330 is used in one embodiment to filter the light from the BLU into the R, G, and B colors. The color filter 330 is formed on a region of the upper substrate 310 corresponding to the pixel electrode 132 on the lower substrate 110. The reason is that light can only be transmitted in the portion of the liquid crystal display 1000 where the pixel electrode 132 is located on the lower substrate 110.

[0084] The methods of forming the color filter 330 include a dye method and a pigment method according to the material used for manufacturing the color filter 330. Some manufacturing methods are a dyeing method, a pigment dispersion method, an electro deposition method, and a printing method, etc. The pigment dispersion method is generally used.

[0085] As shown in FIG. 1, the color filter 330 includes a first color filter 331 for the transmission region and a second color filter 332 for the reflective region.

[0086] In the conventional liquid crystal display, the reflective region corresponding to the lower electrode 131 of the storage capacitor 130 cannot be formed with the color filter 330. The reason is that in the conventional liquid crystal display as described above, the storage capacitor 130 cannot reflect light. However, in the liquid crystal display 1000, the lower electrode 131 of the storage capacitor 130 is used as the reflective electrode to allow the reflected light to transmit through the upper substrate 310. Accordingly, the second color filter 332 can be formed on the reflective region of the upper substrate 310 corresponding to the storage capacitor 130. Also, in some embodiments, the second color filter 332 is not formed on the transparent upper substrate 310 in the reflective region.

[0087] In other words, unlike the conventional liquid crystal display, the black matrix 320 is not formed in the reflective region, and the second color filter 332 may be formed in the reflective region of the upper substrate 310, instead of forming the black matrix 320 in the reflective region corresponding to the storage capacitor 130. Accordingly, the light reflected from the storage capacitor 130 can be transmitted through the upper substrate 310 so that the aperture ratio of the liquid crystal display 1000 can be improved.

[0088] The common electrode 340 is formed on the black matrix 320 and the color filter 330 on the upper substrate 310. The common electrode 340 is used to apply a voltage to the liquid crystal 210 and is formed of a transparent material in order to transmit the light therethrough. The common electrode 340 is formed similarly as the pixel electrode 132 described above except that the common electrode 340 is also formed over the thin film transistor 120. Accordingly, the description of the common electrode 340 will be omitted.

[0089] Although not shown in the drawings, the common electrode 340 is also printed with the alignment film so as to constantly maintain the direction of the liquid crystal 210, and the rubbing process is performed on the alignment film. Since the alignment film printing and rubbing processes are the same as those described in reference to the lower electrode 131, the description thereof will be omitted.

[0090] Also, although not shown in the drawings separately, a seal printing process is performed on the upper substrate 310 after the common electrode 340 is formed. A sealant used for the seal printing process is used to make a liquid crystal cell between the upper substrate 310 and the lower substrate 110. After the upper substrate 310 and the lower substrate 110 are formed, they are bonded. Prior to implanting (e.g., injection) the liquid crystal 210, the bonded substrates are cut into panels. Then, the liquid crystal 210 is implanted into each of the panels, and each panel is sealed by the sealant to create the liquid crystal cell between the substrates. The sealant protects the liquid crystal cell from the external environment. Examples of the material of the sealant includes thermosetting resin and UV-curing resin.

[0091] As described above, the liquid crystal display 1000 uses the lower electrode 131 of the storage capacitor 130 as the reflective electrode so that a separate reflective electrode is not needed, thereby making it possible to remove the step of forming the mask for the separate reflective electrode.

[0092] In the liquid crystal display 1000, the black matrix 320 is not formed in the reflective region in the region corresponding to the storage capacitor 130, and the second color filter 332 is formed in the reflective region, thereby making it possible to increase brightness of the liquid crystal display 1000.

[0093] Hereinafter, a liquid crystal display 2000 according to another embodiment of the present invention will be described.

[0094] FIG. 2 shows a cross-sectional view of the liquid crystal display 2000 according to another embodiment of the present invention.

[0095] As shown in FIG. 2, the liquid crystal display 2000 includes the lower substrate 110, the thin film transistor 120, the storage capacitor 130, the spacer 140, the liquid crystal 210, the upper substrate 310, the black matrix 320, the color filter 330, the common electrode 340, and an organic film 350 formed on the common electrode 340.

[0096] As shown in FIG. 2, the liquid crystal display 2000 is substantially the same as the liquid crystal display 1000

except that the liquid crystal display 2000 includes the organic film 350. The same components and operations in FIGS. 1 and 2 are denoted by the same reference numerals. The following description will be made based on the differences between FIG. 1 and FIG. 2.

[0097] Referring to FIG. 2, the organic film 350 is formed in a region corresponding to the storage capacitor 130 on the upper substrate 310. More specifically, the common electrode 340 is formed on the upper substrate 310, and the organic film 350 is then formed in the region corresponding to the lower electrode 131 of the storage capacitor 130 on the common electrode 340.

[0098] The organic film 350 is provided to constantly maintain the ratio of the distance traveled through the liquid crystal 210 by the light reflected from the lower electrode 131 to the distance traveled through the liquid crystal 210 by the light passing through the first color filter 331 of the transmission region. In other words, the organic film 350 forms a dual cell gap.

[0099] The distance from the lower substrate 110 to the upper substrate 310 is referred to as a cell gap. Also, in order to constantly maintain the ratio of the distanced traveled by the light transmitting through the lower substrate 110 from the backlight unit to the distance traveled by the light reflected from the lower substrate 110, the cell gaps between the upper substrate 310 and the lower substrate 110 should be formed to be different in different regions. The differently formed cell gaps are referred to as a dual cell gap.

[0100] Referring to FIG. 2, when the external light enters the liquid crystal display 2000 through the upper substrate 310 and reaches the lower electrode 131 through the organic film 350, it is reflected and travels through the organic film 350 again. Accordingly, the distance that the external light travels through the liquid crystal 210 is reduced due to the presence of the organic film 350, as compared to the distance traveled in the case where the organic film 350 is not present.

[0101] By forming the organic film 350 with a suitable thickness, the distance traveled by the external light can be made to be equal to the distance traveled by the light transmitted through the lower substrate 110 from the BLU and reaching the transmission region formed with the color filter 331.

[0102] When comparing the thickness of the organic film 350 with the thickness of the liquid crystal 210, in some embodiments, the thickness of the organic film 350 is about half of the thickness of the liquid crystal 210. If the organic film 350 has half of the thickness of the liquid crystal 210, a portion of the liquid crystal 210 below the organic film 350 also has half of the thickness of the liquid crystal 210 in regions without the organic film 350. Accordingly, the distance traveled by the external light can theoretically be made to be equal to the distance traveled by the light transmitted from the BLU. If the distance traveled by the reflected external light is equal to the distance traveled by the light transmitted from the BLU, that is, if the distance traveled by the light in the transmission region is equal to the distance traveled by the light in the reflective region, the transmission efficiency of each light is substantially the same so that the same brightness can be obtained. Accordingly, in some embodiments, the organic film 350 has half of the thickness of the liquid crystal 210. Also, as to the material of the organic film 350, any suitable material capable of performing photolithography such as acrylic based resin can be used.

[0103] As described above, in the liquid crystal display 2000, the organic film 350 is provided to control the distance traveled by the reflected external light and the distance traveled by the light from the BLU, thereby making it possible to obtain substantially the same transmission efficiency and brightness.

[0104] Referring to FIG. 3, a liquid crystal display 3000 according to yet another embodiment of the present invention will be described.

[0105] FIG. 3 is a cross-sectional view illustrating a structure of the liquid crystal display 3000.

[0106] Referring to FIG. 3, the liquid crystal display 3000 includes the lower substrate 110, the thin film transistor 120, the storage capacitor 130, the spacer 140, the liquid crystal 210, the upper substrate 310, the black matrix 320, the color filter 330, a common electrode 345, and an organic film 355.

[0107] The difference between the liquid crystal display 3000 and the liquid crystal display 2000 is that the organic film 355 is formed on the upper substrate 310 first, and then the common electrode 345 is formed. In other words, the embodiment illustrated in FIG. 3 is substantially the same as the embodiment illustrated in FIG. 2 except for the order in which the organic film 355 and the common electrode 345 are formed. The same components and operations in FIGS. 2 and 3 are denoted by the same reference numerals. The following description will be made based on the differences between FIGS. 2 and 3.

[0108] The organic film 355 is formed on a region of the color filter 330 corresponding to the storage capacitor 130, that is, in the reflective region, after the black matrix 320 and the color filter 330 are formed on the upper substrate 310. Accordingly, the organic film 355 is formed on the upper substrate 310 in the reflective region, and the black matrix 320 is not in the reflective region. Also, the color filter 330 is formed in the reflective region.

[0109] The organic film 355 is formed to provide the dual cell gap, as the organic film 350 does in the liquid crystal display 2000 shown in FIG. 2. Accordingly, since the organic film 355 is substantially the same as the organic film 350 in the liquid crystal display 2000, the description of the organic film 355 in the liquid crystal display 3000 will be omitted.

[0110] The common electrode 345 is formed over the upper substrate 310 after the organic film 355 is formed. In other words, the common electrode 345 is formed at the end of the manufacturing process of the upper substrate 310. In other words, the common electrode 345 is substantially the same as the common electrode 340 in the liquid crystal display 2000 of FIG. 2 except that the common electrode 345 is formed after the organic film 355 is formed. Thereafter, the alignment film is printed on the common electrode 345, and the rubbing process is performed thereon. The seal printing process is substantially the same as the process described in reference to FIGS. 1 and 2. Therefore, redundant description of the common electrode 345 will be omitted.

[0111] Hereinafter, the manufacturing order of the liquid crystal display 1000 according to one embodiment of the present invention will be described.

[0112] FIG. 4 shows a flow diagram for explaining a manufacturing order of the liquid crystal display 1000 according to one embodiment of the present invention.

[0113] Referring to FIG. 4, the manufacturing order of the liquid crystal display 1000 includes the steps of: providing a lower substrate S1; forming a thin film transistor and a storage capacitor S2; dispersing a spacer S3; providing an upper

substrate **S4**; forming a black matrix and a color filter **S5**; bonding the lower substrate and the upper substrate **S6**; implanting (or injecting) a liquid crystal **S7**; and encapsulating **S8**.

[0114] The step **S1** of providing the lower substrate provides the lower substrate **110**, which is an original plate, formed with the thin film transistor **120**. Since the light of the BLU is transmitted as described above, the material of the lower substrate **110** should be transparent and may be formed of glass. It is previously mentioned that a fusion method or a floating method may be used as a method of making the glass for the lower substrate **110**.

[0115] The step **S2** of forming the thin film transistor and the storage capacitor forms the thin film transistor **120** and the storage capacitor **130** on the upper side of the lower substrate **110**. The thin film transistor **120** is constituted by the gate electrode **121**, the gate insulating layer **122**, the silicon layer **123**, the source/drain electrode **125**, and the protective layer **126**. The detailed description of the process for forming the thin film transistor **120** and the storage capacitor **130** will be described later. Also, although not shown separately, the step of forming the alignment film follows the step **S2** of forming the thin film transistor and the capacitor. Thereafter, the rubbing process of the alignment film can be performed.

[0116] The step **S3** of dispersing the spacer forms the spacer **140** on the upper side of the lower substrate **110**. The spacer **140** is formed to maintain a suitable gap (e.g., a predetermined gap) between the upper and lower substrates **310** and **110** as described above. As to the methods of forming the spacer **140**, there are a dry method and a wet method as described above.

[0117] The step **S4** of providing the upper substrate provides the upper substrate **310**, which is an original plate for the black matrix **320** and the color filter **330**. The upper substrate **310** should be transparent so that it can transmit light. Therefore, in some embodiments, glass is used for the upper substrate **310**. Since the upper substrate **310** is substantially the same as the lower substrate **110**, the description thereof will be omitted.

[0118] The step **S5** of forming the black matrix and the color filter forms the black matrix **320** and the color filter **330** on the upper substrate **310**. In the liquid crystal display **1000**, the black matrix **320** located on the upper substrate **310** is not formed (or removed) from the reflective region corresponding to the storage capacitor **130**, and, in some embodiments, the second color filter **332** is formed in the reflective region. Accordingly, the step **S5** of forming the black matrix and the color filter forms the black matrix **320** and the color filter **330** using the mask formed with a pattern so that light can be transmitted into the region of the upper substrate **310** corresponding to the storage capacitor **130**.

[0119] After the step **S5** of forming the black matrix and the color filter, it is previously mentioned that the seal printing process for printing the sealant can be carried out. The liquid crystal cell can be formed in the panel that includes the upper substrate **310** and the lower substrate **110** through the cell printing process.

[0120] The step **S6** of bonding the upper and lower substrates bonds the upper substrate **310** and the lower substrate **110** together. A substantially constant gap between the two substrates is maintained by the spacer **140**. After the step **S6** of bonding the upper and lower substrates, the bonded substrates can be divided in a cutting process into panels. The cutting process is not shown separately in FIG. 4.

[0121] The step **S7** of implanting (or injecting) the liquid crystal implants the liquid crystal **210** into the space between the bonded substrates of the divided panels. The substrates of the panels are provided with the liquid crystal cells. An exemplary method that can efficiently implants the liquid crystal **210** into the liquid crystal cell is a vacuum implantation method that uses a pressure difference between inside and outside of the liquid crystal cell to implant the liquid crystal **210**.

[0122] The encapsulating step **S8** prevents the liquid crystal **210** from leaking out of an inlet of the liquid crystal cell after the implantation of the liquid crystal **210** is completed. The inlet is usually sealed by coating the inlet with an ultraviolet ray curable resin using a dispenser and then irradiating the resin with an ultraviolet ray.

[0123] Hereinafter, an exemplary manufacturing process of a liquid crystal display according to one embodiment of the present invention will be described using a cross-sectional view.

[0124] FIGS. 5a to 5f show cross-sectional views for explaining the manufacturing process according to one embodiment of the present invention.

[0125] FIG. 5a shows the lower substrate **110**. The lower substrate **110** is formed of glass, and its thickness is between about 0.5 to 0.7 mm.

[0126] Referring to FIG. 5b, on the upper side of the lower substrate **110** the gate electrode **121** of the thin film transistor **120** and the lower electrode **131** of the storage capacitor **130** are formed. The gate electrode **121** and the lower electrode **131** may be formed of the same material or different material. However, since the liquid crystal display **1000** according to one embodiment of the present invention uses the lower electrode **131** as the reflective electrode, the lower electrode **131** can be formed using Al, AlNd, Mo, Cr, Mo/AlNd(double), MoW, or an equivalent thereof. In order for the gate electrode **121** and the lower electrode **131** to be formed using different material, an additional masking process is used.

[0127] Referring to FIG. 5c, the gate insulating layer **122** is over the gate electrode **121** and the lower electrode **131**. The gate insulating layer **122** may be deposited using, for example, silicon nitride SiN_x. The gate insulating layer **122** may be formed by, for example, the PECVD method.

[0128] Referring to FIG. 5d, on the gate insulating layer **122**, the silicon layer **123** is formed. It is previously mentioned that the silicon layer **123** may be formed, for example, using amorphous silicon (a-Si) because the glass of the lower substrate **110** is amorphous, or may use poly silicon (poly-Si) in order to increase electron mobility.

[0129] Referring to FIG. 5e, on the upper side of the silicon layer **123**, the semiconductor layer **124** and the source/drain electrode **125** are formed.

[0130] The semiconductor layer **124** can be formed by doping impurities using a mask after forming the silicon layer **123**. For example, the ion implantation method can be used as the method for doping the impurities.

[0131] After forming the semiconductor layer **124**, the source/drain electrode **125** is formed by depositing a metal layer on the lower substrate **110** and then etching it in a desired pattern using a mask.

[0132] Referring to FIG. 5f, the protective layer **126** is formed on the lower substrate **110** over the source/drain electrode **125**. The protective layer **126** can be etched in a desired pattern using a mask after depositing the protective layer material over the lower substrate **110**. Referring to FIG. 5f, it

can be appreciated that a portion of the protective layer **126** on the upper surface of the source/drain electrode **125** is etched away to provide a via hole to allow an electrical connection between the source/drain electrode **125** and the pixel electrode **132** shown in FIG. **5g**.

[0133] Referring to FIG. **5g**, on the lower substrate **110**, the pixel electrode **132** is formed. Since the pixel electrode **132** should be transparent to be able to transmit light, it may be made of, for example, indium tin oxide (ITO). As shown in FIG. **5g**, the pixel electrode **132** can be used as the upper electrode of the storage capacitor **130**.

[0134] Although not shown separately, after the pixel electrode **132** is formed, the alignment film printing and rubbing processes are performed in order to constantly maintain the direction of the liquid crystal **210**.

[0135] Referring to FIG. **5h**, space **140** is formed on the upper surface of the protective layer **126**. Since the spacer **140** does not transmit light, it is formed at a region on the upper side of the thin film transistor **120** that is not capable of transmitting light, in order to raise the aperture ratio. The spacer **140** protects the liquid crystal **210** by bonding the lower substrate **110** to the upper substrate **310** and then constantly maintaining a gap therebetween. Since the material and the manufacturing process of the spacer **140** are described in the foregoing description, the description thereof will be omitted.

[0136] Referring to FIG. **5i**, there is shown the upper substrate **310**. The method of forming the upper substrate **310** is the same as that of the lower substrate **110** as described above.

[0137] Referring to FIG. **5j**, on the upper surface of the upper substrate **310** are the black matrix **320** and the color filter **330**. The black matrix **320** is formed in the region corresponding to the thin film transistor **120** of the lower substrate **110**, and the color filter **330** is formed on a region of the upper substrate **310** other than the region of the black matrix **320**. Only the black matrix **320** is removed from (or not formed in) the reflective region of the upper substrate **310** corresponding to the storage capacitor **130** on the lower substrate **110**. In some embodiments, the color filter **330** can be formed in the reflective region.

[0138] Referring to FIG. **5k**, the common electrode **340** is on the black matrix **320** and the color filter **330**. Since the common electrode **340** is formed in substantially the same manner as the pixel electrode **132**, except that the common electrode **340** is formed over the upper substrate **310**, the description thereof will be omitted.

[0139] Although not shown separately, the alignment film printing and rubbing processes are further performed in order to constantly maintain the direction of the liquid crystal **210** after the common electrode **340** is formed. Also, after these processes, the seal printing process is performed in order to form the liquid crystal cell.

[0140] Referring to FIG. **5l**, as a final process the upper substrate **310** and the lower substrate **110** are bonded, and the bonded substrates are cut into panels. The gap between the upper substrate **310** and the lower substrate **110** is constantly maintained by the spacer **140**, and the liquid crystal **210** is implanted (or injected) into the space between the substrates. An exemplary method for implanting the liquid crystal **210** is the vacuum implantation method described above.

[0141] Hereinafter, the manufacturing order of the liquid crystal display **2000** according to another embodiment of the present invention and the liquid crystal display **3000** accord-

ing to yet another embodiment of the present invention will be described using a flow diagram.

[0142] FIG. **6** is a flow diagram for explaining a manufacturing order of the liquid crystal display **2000** and the liquid crystal display **3000**.

[0143] Referring to FIG. **6**, the manufacturing order of the liquid crystal displays **2000** and **3000** according to the embodiments of the present invention includes the following steps: providing a lower substrate **S1**; forming a thin film transistor and a storage capacitor **S2**; forming a spacer **S3**; providing an upper substrate **S4**; forming a black matrix and a color filter **S5**; bonding the lower substrate and the upper substrate **S6**; implanting (or injecting) a liquid crystal **S7**; encapsulating **S8**; and forming an organic film **S5-1** after forming the black matrix and the color filter.

[0144] In other words, as compared to the manufacturing order of the liquid crystal display **1000** according to one embodiment of the present invention of FIG. **4**, the only difference is that the step **S5-1** of forming organic film is further provided after the step **S5** of forming the black matrix and the color filter. The same components and operations are denoted by the same reference numerals. The following description will be made based on the difference.

[0145] The step **S5-1** of forming the organic film is further provided after the step **S5** of forming the black matrix and the color filter as described above. In other words, the organic film **350** is formed on the upper substrate **310** after forming the black matrix **320** and the color filter **330**. As previously described, the organic film **350** should be formed on a region of the upper substrate **310** corresponding to the lower electrode **131** of the storage capacitor **130**. In order to form the organic film **350** in a desired pattern, the photolithography method can be used. Also, any material to which the photolithography method can be applied can be used as the material of the organic film **350**. Also, the organic film **350** is formed to provide the dual cell gap as described above.

[0146] Since processes other than the organic film forming process are substantially the same as the corresponding processes for manufacturing the liquid crystal display **1000** according to one embodiment of the present invention described above, the description thereof will be omitted.

[0147] Hereinafter, the manufacturing process of the liquid crystal display **3000** according to yet another embodiment of the present invention will be described using a cross-sectional view.

[0148] FIGS. **7a** to **7e** show cross-sectional views of the liquid crystal display **3000** for explaining the manufacturing process of the upper substrate **310** in the manufacturing process of the liquid crystal display **3000**. Only the manufacturing process of the upper substrate **310** is described because the lower substrate **110** of the liquid crystal display **3000** is substantially the same as the lower substrate **110** of the liquid crystal display **1000** described above.

[0149] Referring to FIG. **7a**, there is shown the upper substrate **310**. The upper substrate **310** may be formed of glass.

[0150] Referring to FIG. **7b**, on the upper substrate **310**, the black matrix **320** and the color filter **330** are formed. The black matrix **320** is formed on the non-reflective region of the upper substrate **310** corresponding to the thin film transistor **120** on the lower substrate **110**. Also, the black matrix **320** is not formed on the reflective region of the upper substrate **310** corresponding to the storage capacitor **130**. Also, it is previously mentioned that the color filter **330** can be formed on the

reflective region of the upper substrate **310** corresponding to the storage capacitor **130** in some embodiments.

[0151] Referring to FIG. 7c, the organic film **355** is formed on the upper substrate **310** on which the black matrix **320** and the color filter **330** are formed. The organic film **355** is formed on the reflective region of the upper substrate **310** corresponding to the storage capacitor **130** on the lower substrate **110**. In order to form the pattern, the photolithography process can be used. It is previously mentioned that the organic film **350** provides the dual cell gap structure.

[0152] Referring to FIG. 7d, the common electrode **345** is formed on the upper substrate **310** on which the organic film **355** is formed. The common electrode **345** is formed over the upper substrate **310**.

[0153] Although not shown separately, after the common electrode **345** is formed, the alignment printing process, the rubbing process and the seal printing process can further be performed.

[0154] Referring to FIG. 7e, the processes for bonding the upper substrate **310** and the lower substrate **110**, cutting the bonded substrates into panels, and implanting the liquid crystal **210** into the cut substrates are performed. Also, the encapsulating process is performed to prevent the liquid crystal **210** from leaking out of the inlet of the liquid crystal cell by which the implantation of the liquid crystal **210** is completed. The inlet may be sealed by coating it with an ultraviolet ray curable resin using the dispenser and then irradiating the coating with the ultraviolet ray.

[0155] According to the above description, the liquid crystal display **3000** can be manufactured. Also, although not shown and described separately, the difference between the liquid crystal displays **2000** and **3000** is in the order of forming the organic films **350** and **355** and the common electrodes **240** and **245**. Accordingly, referring to the manufacturing method of the liquid crystal display **3000**, those skilled in the art to which the present invention pertains can manufacture the liquid crystal display **2000** according to other embodiments of the present invention, and the description thereof will be omitted.

[0156] A liquid crystal display according to the embodiments of the present invention uses the metal electrode of the storage capacitor as the reflector so that the manufacturing process of a separate reflective electrode can be avoided.

[0157] According to the described embodiments, a liquid crystal display for displaying images can include a color filter on the reflective region of the upper substrate corresponding to the storage capacitor on the lower substrate that reflects light in the reflective region.

[0158] Further, according to the embodiments, the image quality of the reflective region can be improved by forming the organic film for the dual cell gap structure on the reflective region of the upper substrate corresponding to the storage capacitor on the lower substrate.

[0159] In addition, according to the embodiments, the transreflective liquid crystal display can be manufactured at a low cost by a suitable process.

[0160] While the present invention has been described in connection with certain exemplary embodiments, it is to be understood that the invention is not limited to the disclosed embodiments, but, on the contrary, is intended to cover various modifications and equivalent arrangements included within the spirit and scope of the appended claims, and equivalents thereof.

What is claimed is:

1. A liquid crystal display comprising:

- a first substrate;
 - a second substrate spaced apart from and facing the first substrate;
 - a thin film transistor on a side facing the second substrate of the first substrate;
 - a storage capacitor on the side facing the second substrate of the first substrate;
 - a black matrix on a side facing the first substrate of the second substrate;
 - a color filter on the side facing the first substrate of the second substrate; and
 - liquid crystals between the first substrate and the second substrate,
- wherein the storage capacitor comprises a reflective electrode configured to reflect external light received through the first substrate.

2. The liquid crystal display as claimed in claim 1, wherein the storage capacitor further comprises a pixel electrode.

3. The liquid crystal display as claimed in claim 2, wherein the reflective electrode of the storage capacitor comprises any one selected from Al, AlNd, Mo, Cr, Mo/AlNd(double), MoW, and equivalent thereof.

4. The liquid crystal display as claimed in claim 1, wherein the color filter is on a reflective region of the second substrate, and the reflective region corresponds to the storage capacitor on the first substrate.

5. The liquid crystal display as claimed in claim 1, wherein the black matrix is on a region of the second substrate that is different from a reflective region of the second substrate, and the reflective region corresponds to the storage capacitor on the first substrate.

6. A liquid crystal display comprising:

- a first substrate;
- a second substrate spaced apart from and facing the first substrate;
- a thin film transistor on a side facing the second substrate of the first substrate;
- a storage capacitor on the side facing the second substrate of the first substrate, the storage capacitor comprising a reflective electrode configured to reflect external light through the first substrate;
- a black matrix on a side facing the first substrate of the second substrate;
- a color filter on the side facing the first substrate of the second substrate;
- an organic film on a reflective region of the second substrate, the reflective region corresponding to the storage capacitor on the first substrate; and
- liquid crystals between the first substrate and the second substrate.

7. The liquid crystal display as claimed in claim 6, wherein the organic film is on the color filter in the reflective region.

8. The liquid crystal display as claimed in claim 6, wherein the organic film is on the reflective region of the second substrate that is different from another region of the second substrate in which the black matrix and the color filter are located.

9. The liquid crystal display as claimed in claim 6, further comprising a common electrode on the black matrix and the color filter, and the organic film is on the common electrode.

10. The liquid crystal display as claimed in claim 6, further comprising a common electrode on the black matrix, the color filter and the organic film.

11. The liquid crystal display as claimed in claim 6, wherein a thickness of the organic film is one half the total thickness of the liquid crystals.

12. The liquid crystal display as claimed in claim 6, wherein the organic film provides a path traveled by a reflected light through the liquid crystals in the reflective region, and

wherein a distance traveled by the reflected light within the liquid crystals is equal to a distance traveled by a transmitted light within the liquid crystals in a transmission region.

13. A manufacturing method of a liquid crystal display, the method comprising:

forming a thin film transistor and a storage capacitor on a first substrate, the storage capacitor having a reflective electrode;

providing a second substrate facing the first substrate;

forming a black matrix and a color filter on a side facing the first substrate of the second substrate;

bonding the lower substrate and the second substrate together; and

implanting liquid crystals between the bonded first and second substrates.

14. The manufacturing method of a liquid crystal display as claimed in claim 13, wherein the storage capacitor further comprises a pixel electrode.

15. The manufacturing method of a liquid crystal display as claimed in claim 14, wherein the reflective electrode of the storage capacitor comprises anyone selected from one of Al, AlNd, Mo, Cr, Mo/AlNd(double), MoW, and equivalents thereof.

16. The manufacturing method of a liquid crystal display as claimed in claim 13, wherein the color filter is on a reflective region of the second substrate, the reflective region corresponding to the storage capacitor on the first substrate.

17. The manufacturing method of a liquid crystal display as claimed in claim 13, wherein the black matrix and the color filter are on a region of the second substrate other than the reflective region corresponding to the storage capacitor on the first substrate.

18. A manufacturing method of a liquid crystal display, the method comprising:

forming a thin film transistor and a storage capacitor on a first substrate, the storage capacitor comprising a reflective electrode;

forming a black matrix and a color filter on a side facing the first substrate on a second substrate;

forming an organic film on a reflective region on the side facing the first substrate of the second substrate, the reflective region corresponding to the storage capacitor on the first substrate;

bonding the first substrate and the second substrate together; and

implanting liquid crystals between the bonded upper and lower substrates.

19. The manufacturing method of a liquid crystal display as claimed in claim 18, wherein the organic film is on the color filter, the organic film corresponding to the storage capacitor.

20. The manufacturing method of a liquid crystal display as claimed in claim 18, wherein the organic film is on the reflective region, and the black matrix and the color filter are on a region different from the reflective region.

21. The manufacturing method of a liquid crystal display as claimed in claim 18, further providing a common electrode, wherein the common electrode is on the black matrix and the color filter, and the organic film is on the common electrode.

22. The manufacturing method of a liquid crystal display as claimed in claim 18, further providing a common electrode on the black matrix, the color filter, and the organic film.

23. The manufacturing method of a liquid crystal display as claimed in claim 18, wherein a thickness of the organic film has half of the total thickness of the liquid crystals.

24. The manufacturing method of a liquid crystal display as claimed in claim 18, wherein the organic film provides a path traveled by a reflected light through the liquid crystal unit in the reflective region, and

wherein a distance traveled by the reflected light within the liquid crystals is equal to a distance traveled by a transmitted light within the liquid crystals in a transmission region.

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摘要(译)

一种液晶显示器及其制造方法。液晶显示器包括具有金属电极作为反射器的存储电容器。液晶显示器可以包括在与第一基板上的存储电容器对应的第二基板的反射区域上的滤色器和/或黑矩阵。光从反射区域反射，以透过第一和第二基板之间的液晶。有机膜可以在第二基板上。

